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JC17 Rec'd PCT/PTO 20 SEP 2005

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Docket No: Q90414

Hiroyuki AKAGAWA

Appln. No.: Based on PCT/JP2004/003617

Confirmation No.: Unknown

Group Art Unit: Unknown

Filed: September 20, 2005

Examiner: Unknown

For: SUBSTRATE FOR RETICLE AND METHOD FOR MANUFACTURING SUBSTRATE,
AND MASK BLANK AND METHOD FOR MANUFACTURING MASK BLANK

INFORMATION DISCLOSURE STATEMENT
UNDER 37 C.F.R. §§ 1.97 and 1.98

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

In accordance with the duty of disclosure under 37 C.F.R. § 1.56, Applicant hereby notifies the U.S. Patent and Trademark Office of the documents which are listed on the attached PTO/SB/08 A & B (modified) form and/or listed herein and which the Examiner may deem material to patentability of the claims of the above-identified application.

One copy of each of the listed documents is submitted herewith, except for the following: U.S. patents and/or U.S. patent publications; and co-pending non-provisional U.S. applications filed after June 30, 2003.

The present Information Disclosure Statement is being filed: (1) No later than three months from the application's filing date; (2) Before the mailing date of the first Office Action on the merits (whichever is later); or (3) Before the mailing date of the first Office Action after

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filing a request for continued examination (RCE) under §1.114, and therefore, no Statement under 37 C.F.R. § 1.97(e) or fee under 37 C.F.R. § 1.17(p) is required.

In compliance with the concise explanation requirement under 37 C.F.R. § 1.98(a)(3) for foreign language documents, Applicant encloses herewith a copy of a Communication from a foreign patent office in a counterpart application citing such documents, together with an English-language version (if not already included) of at least that portion of the Communication indicating the degree of relevance found by the foreign patent office. Additionally, English abstracts, submitted herewith, constitute concise statements of relevance for JP 2003-64-40267, JP 2002-318450, JP 2003-51472, JP 2002-162726, JP 2004-54285 and JP 2004-29735.

The submission of the listed documents is not intended as an admission that any such document constitutes prior art against the claims of the present application. Applicant does not waive any right to take any action that would be appropriate to antedate or otherwise remove any listed document as a competent reference against the claims of the present application.

The USPTO is directed and authorized to charge all required fees, except for the Issue Fee and the Publication Fee, to Deposit Account No. 19-4880. Please also credit any overpayments to said Deposit Account. A duplicate copy of this paper is attached.

Respectfully submitted,

A handwritten signature in black ink, appearing to read "Alan J. Kasper", is written over a horizontal line. To the right of the signature, the number "29,710" is handwritten with a small asterisk.

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| Substitute for Form 1449 A & B/PTO | | | | Complete if Known | |
| INFORMATION DISCLOSURE STATEMENT BY APPLICANT <i>(use as many sheets as necessary)</i> | | | | Application Number | Based on PCT/JP2004/003617 |
| | | | | Confirmation Number | Unknown |
| | | | | Filing Date | September 20, 2005 |
| | | | | First Named Inventor | Hiroyuki AKAGAWA |
| | | | | Art Unit | Unknown |
| | | | | Examiner Name | Unknown |
| Sheet | 1 | of | 1 | Attorney Docket Number | Q90414 |

| U.S. PATENT DOCUMENTS | | | | | |
|-----------------------|-----------------------|-----------------|--------------------------------------|--------------------------------|---|
| Examiner Initials* | Cite No. ¹ | Document Number | | Publication Date MM-DD-YYYY | Name of Patentee or Applicant of Cited Document |
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| NON PATENT LITERATURE DOCUMENTS | | | |
|---------------------------------|-----------------------|--|--------------------------|
| Examiner Initials* | Cite No. ¹ | Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city, and/or country where published. | Translation ⁶ |
| | | MASAMITSU ITOH, et al., New Concept of Specification for Mask Flatness, Proceedings of SPIE Photomask and Next-Generation Lithography Mask Technology IX, SPIE Vol. 4754 (2002), 43-53 | |
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*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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